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	Subclass	ISSUE CLASSIFICATION
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PATENT	NUMBER	ì

U.S. UTILITY Patent Application

O.I.P.E.	PATENT DATE			
SCANNED ASO Q.A. AND				

APPLICATION NO. 09/887165 CONT/PRIOR CLASS SUBCLASS ART UNIT

Calvin Gabriel Lynne Okada Ramkumar Subramanian



N-containing plasma etch process with reduced resist poisoning

		ISSUING C	CLASSIFICATION		
ORIGINA	ıL.	CROSS REFERENCE(S)			
CLASS	SUBCLASS	CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)		
INTERNATIONAL	CLASSIFICATION				
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DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
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The term of this patent subsequent to (date)				NOTICE OF ALL	OWANCE MAILED
has been disclaimed.	(Assistant Examiner) (Date)				
The term of this patent shall not extend beyond the expiration date					
of U.S Patent. No.				ISSI	JE FEE
				Amount Due	Date Paid
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